

Notice of References Cited	Application/Control No. 10/621,712	Applicant(s)/Patent Under Reexamination WANG, QI	
	Examiner Alexander G. Ghyska	Art Unit 2812	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
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FOREIGN PATENT DOCUMENTS

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	Q					
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	S					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Osono et al , Coverage Properties of Silicon Nitride Film Prepared by the Cat-CVD Method, Thin Films, April 2003, April 2003
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

Alex Ghyska 4/19/07